



# NewLambda *Technologies*

## **Recent Progress on High-Brightness Source Collector Module for EUV Mask Metrology**

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# NewLambda Technologies

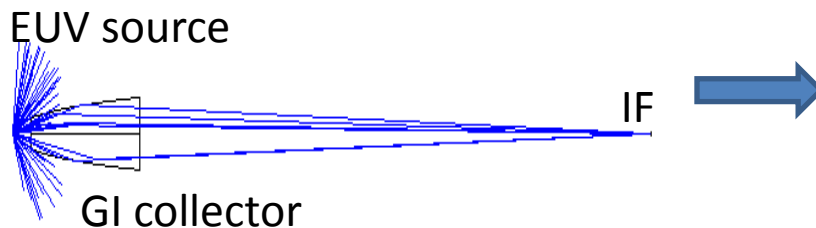
- Spin out from UCD School of Physics, Ireland
- Developing VUV, EUV and Soft X-ray sources
- Applications
  - Metrology
  - Table-top tuneable beamline
  - Microscopy

# Metrology Source Considerations

Tool Requirements*		
Metrology Tool	Etendue	Brightness
AIMS	$5 \times 10^{-4} \text{ mm}^2\text{sr}$	30-100 W/mm <sup>2</sup> sr
Mask Blank	$4 \times 10^{-3} \text{ mm}^2\text{sr}$	> 80 W/mm <sup>2</sup> sr
Patterned Mask	$1.5 \times 10^{-2} \text{ mm}^2\text{sr}$	> 40 W/mm <sup>2</sup> sr

## Choices for etendue matching:

- Demagnify large source – photon loss for fixed etendue
- Magnify small source - higher photon collection  
- higher brightness for given input power



Magnifying ellipsoid (x8)  
Placed < 20 mm from EUV Source  
Etendue  $\geq 10^{-4} \text{ mm}^2\text{sr}$   
High Brightness

# Mask Metrology SoCoMo Status

Parameter	Industry Target Value*		
	AIMS	Blank	Pattern
Brightness (W/mm <sup>2</sup> sr)	30-100	>80	>40
Etendue (mm <sup>2</sup> sr)	5e-4	4e-3	1.5e-2
Position Stability (of FWHM)	3%	3%	3%
Size Stability	3%	3%	3%
Energy Stability	<3%	<3%	<3%-
Homogeneity	<5%	<5%	<5%
Operating time	100	100	100

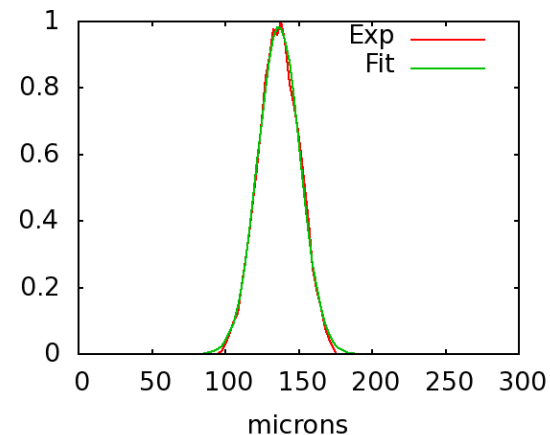
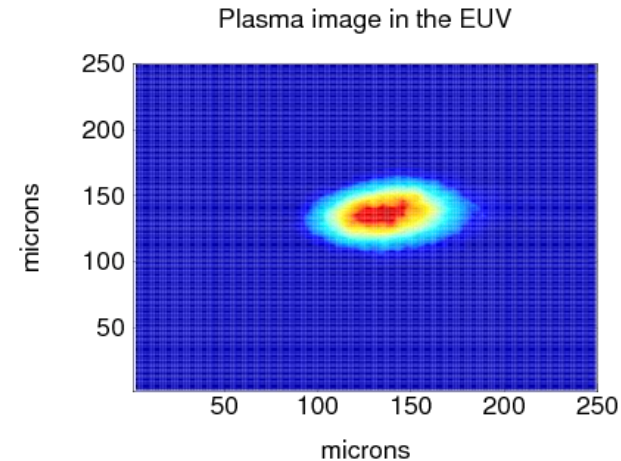
\* EUVL Symposium, 2011

# NLT Source

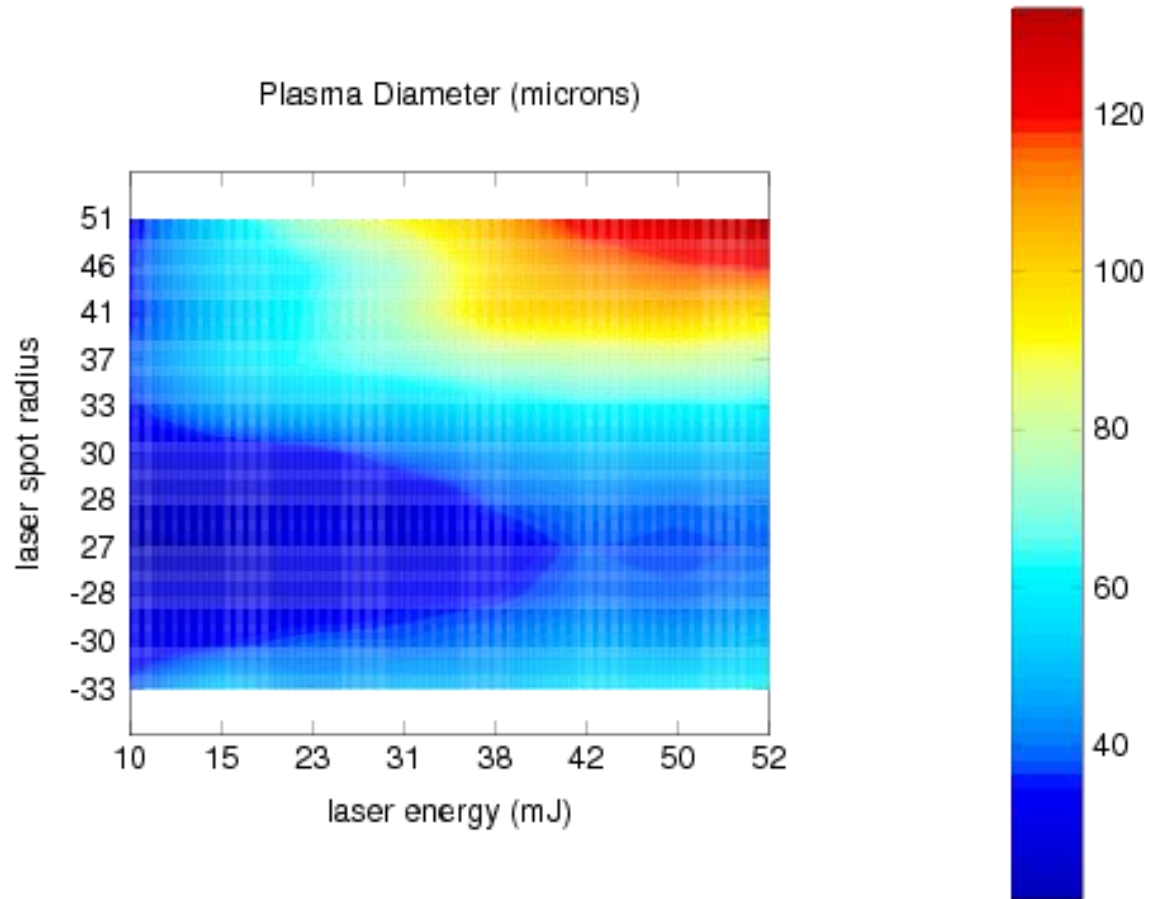
- LPP (Nd:YAG 125W, 25 mJ per pulse, 5 kHz)
- Proprietary liquid metal mixture as target
- Current status:
  - >200 hours total operation (since Nov. 2011)
  - Brightness =  $80 \text{ W/mm}^2\text{sr}$ 
    - (Brightness calculated using the Carl Zeiss method)
  - 24 hours continuous
  - Self-healing collector
  - Roadmap to  $>500 \text{ W/mm}^2\text{sr}$ , 100 hours continuous

# Source Imaging

- Imaged using multilayer concave mirror
- 10 shots per frame
- 34 x 55 micron spot measured
- Gaussian fit

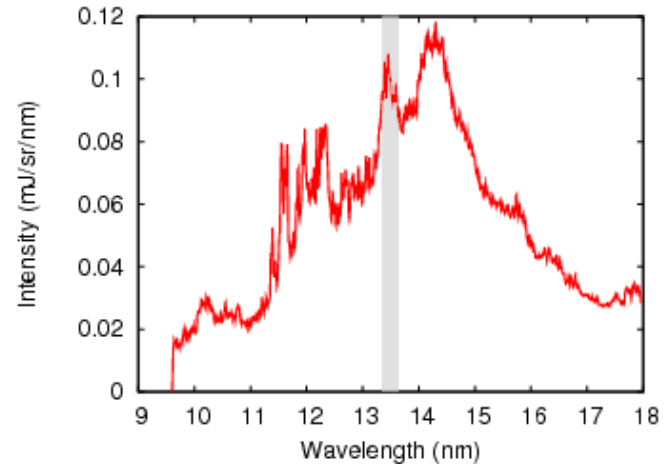


# Source Imaging

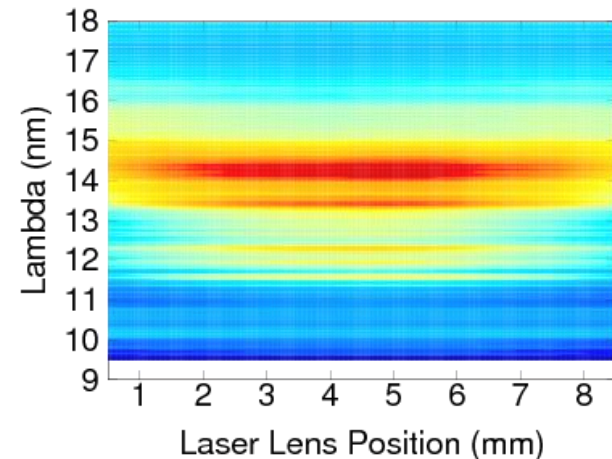


# Source Spectra

- Nd:YAG, 17 mJ per pulse, 1 kHz
- Viewed at  $45^\circ$
- CE > 1% measured



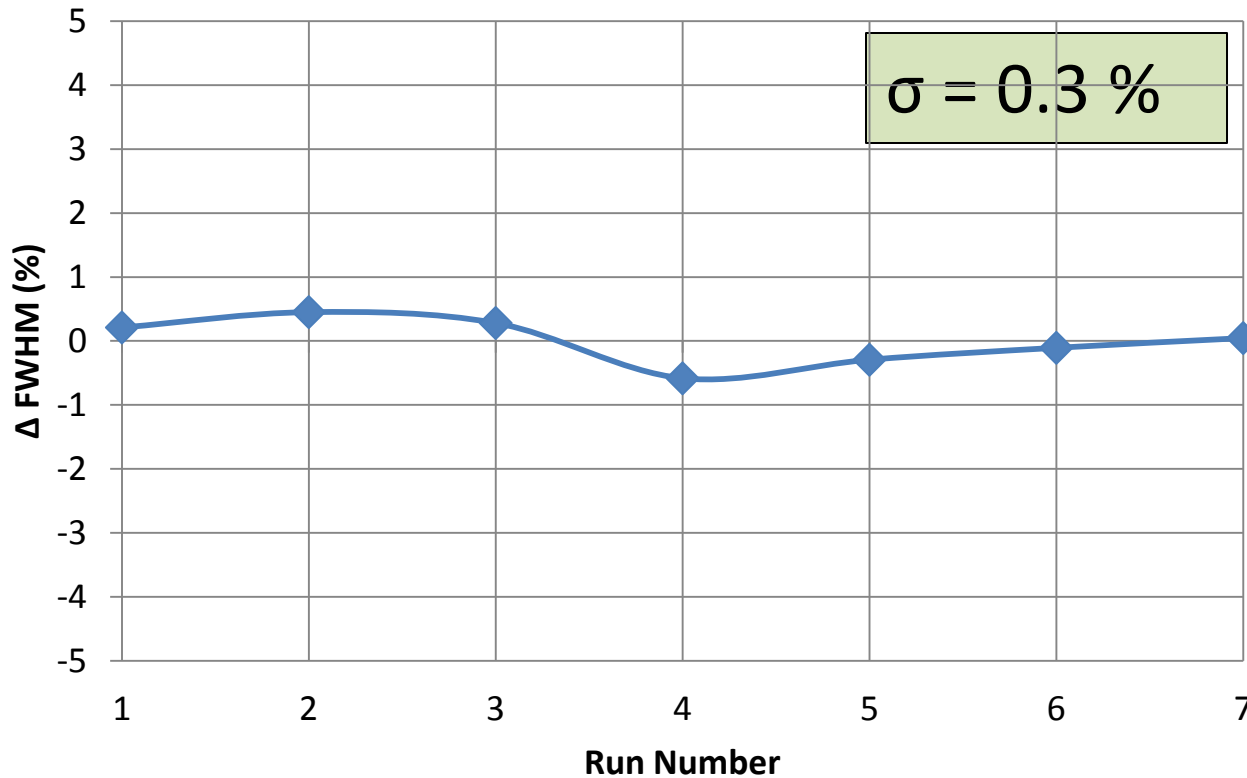
1000 Hz



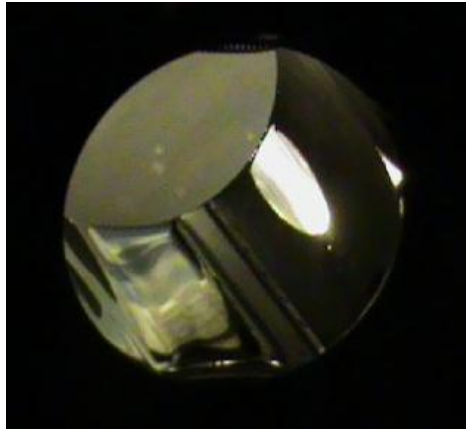


# Stability - Source Position

Imaged with 50  $\mu\text{m}$  pinhole



# The Liquid Metal Collector

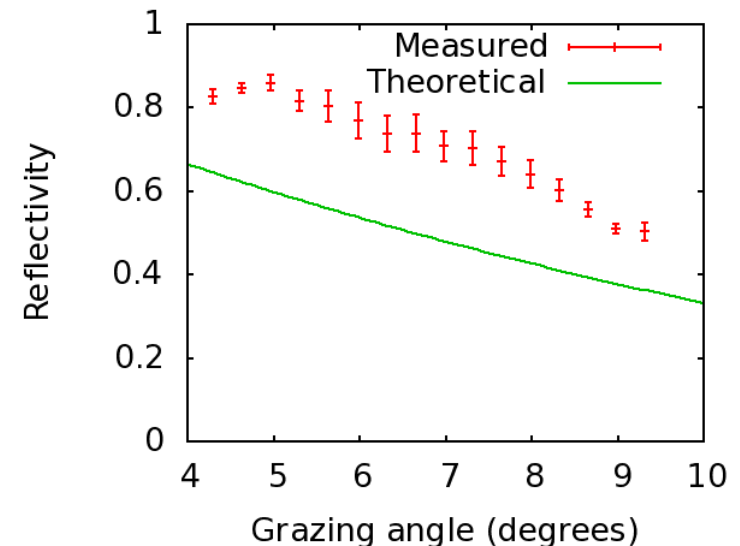
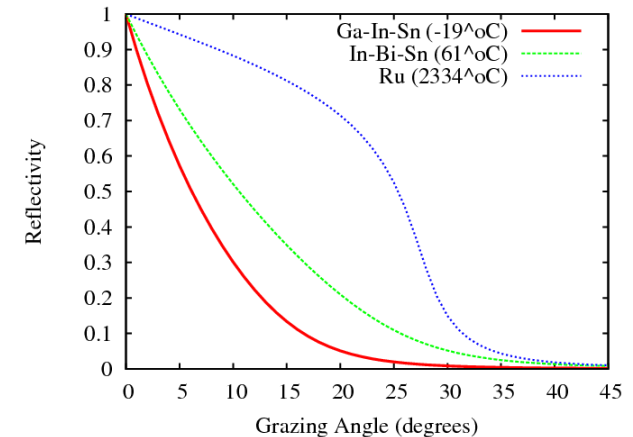


## Collector design example:

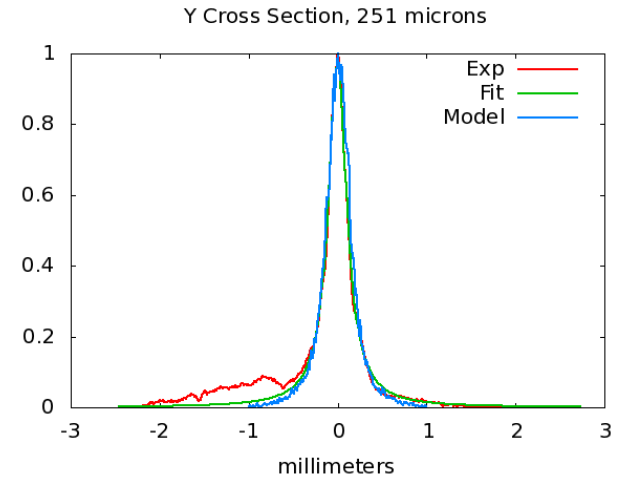
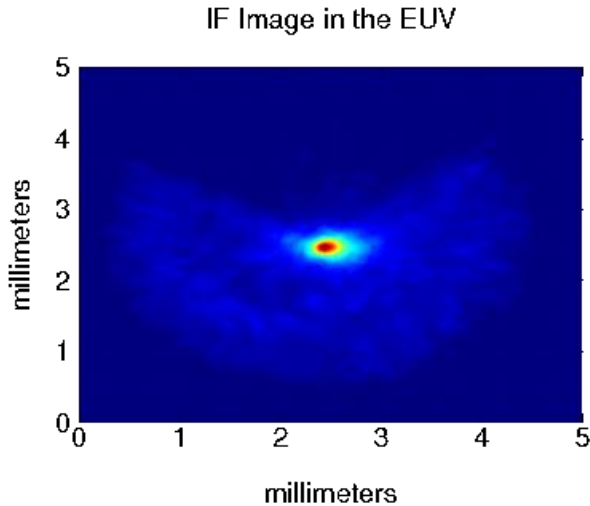
Tin-based coating  
Ellipsoid Shape  
Length = 100 mm  
Large Diameter = 40 mm  
Predicted Collection ~ 3%

## Optimising:

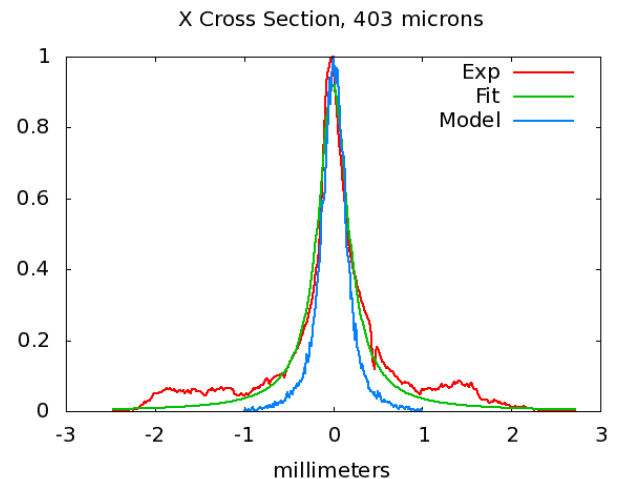
Collection efficiency  
IF brightness



# Intermediate Focus Imaging



- Single Shot Imaging
- Lorentzian fit
- IF spot size 250 x 400 microns



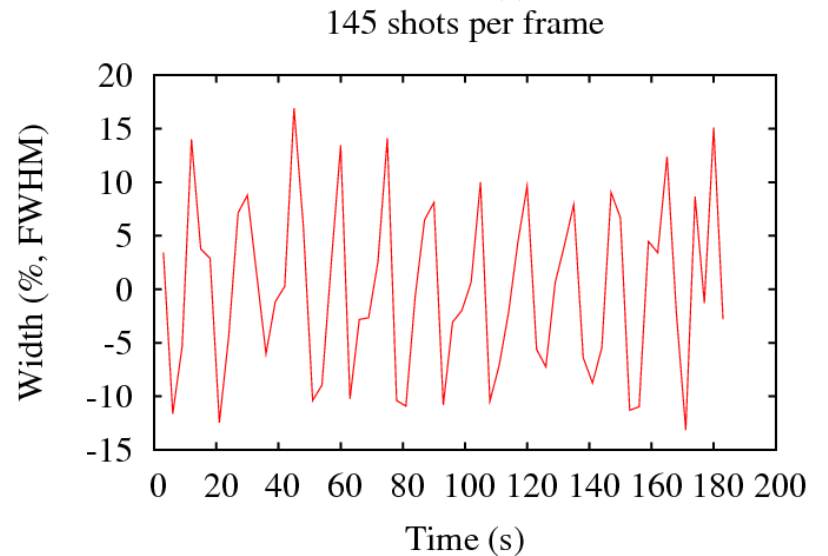
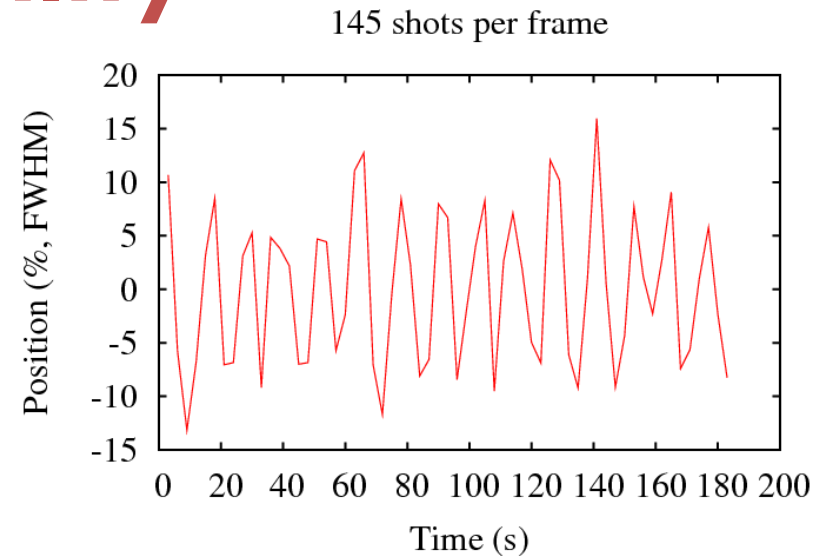
# IF Stability

## Position

- Measured  $\sigma = 7\%$
- Required  $\sigma = 3\%$

## Size

- Measured  $\sigma = 8\%$
- Required  $\sigma = 3\%$



# NLT SoCoMo



- High Brightness LPP
- Clean IF
- Stand Alone Unit
- 1 m x 1 m x 1.2 m
- Multiple parameter monitoring

# Mask Metrology SoCoMo Status

Parameter	Industry Target Value			NewLambda
	AIMS	Blank	Pattern	Current Prototype
Brightness (W/mm <sup>2</sup> sr)	30-100	>80	>40	80
Etendue (mm <sup>2</sup> sr)	5e-4	4e-3	1.5e-2	5e-4
Positional Stability	3%	3%	3%	7%
Size Stability	3%	3%	3%	8%
Energy Stability	<3%	<3%	<3%-	9%
Homogeneity	<5%	<5%	<5%	7.5%
Operating time	100	100	100	>200 total 24 continuous

# Future Plans

- Upgrade Laser to 300 W
- Improve source stability
- Optimising Liquid Metal recipe,  
(CE & Reflectivity)
- Extend Lifetime operation

# Acknowledgements



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Thank you for listening